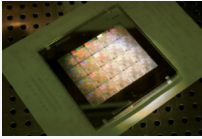



Photolithography patterning

APPLICATIONS

Semiconductor 	<ol style="list-style-type: none"> 1. Electronic circuit formation 2. Dielectric layer formation
Display 	<ol style="list-style-type: none"> 1. Transistor and color filter 2. RGB layer formation (Color Resist)

THEORY, KNOWLEDGE, & MODELS

Theory	Patterning	Photolithography
Process	Coating	<ol style="list-style-type: none"> 1. Spin coating 2. Softbake
	UV exposure	<ol style="list-style-type: none"> 1. Mask alignment 2. UV Exposure
	Develop	<ol style="list-style-type: none"> 1. Develop
Materials		<ol style="list-style-type: none"> 1. General Photoresist 2. Photo sensitive Polyimide

CAPABILITIES

Core Equipment at ADL Ewha site
<ol style="list-style-type: none"> 1. Spin coating on Substrate 2. Mask Alignment and UV Exposure 3. Develop

Core Competitiveness at ADL Ewha

<ol style="list-style-type: none"> 1. Photo Sensitive Material Formulation Testing
<ol style="list-style-type: none"> 2. Coating and Patternability Evaluation
<ol style="list-style-type: none"> 3. Analysis and Reliability Testing

Evaluation Data Library

Commercialized Products	AZ series, JSR Series
Customized Products	

Current Project Introduction

No	Project Title
1	Photo Sensitive PI development at Ewha ADL Team
2	
3	